



Advanced Laser Technologies

Industrial Femtosecond Lasers



FemtoLux Series

Award winning tools for micromachining applications

FemtoLux 30 4

FemtoLux 3 14



2024

Rev#
240201

Industrial Femtosecond Lasers

SPECIFICATIONS AT A GLANCE

Not all output specifications may be available simultaneously. Please refer to the catalog page for exact specifications and available options.

Model	Available output wavelengths	Pulse duration ¹⁾	Max output power ¹⁾	Max repetition rate	Max pulse energy ¹⁾	Page
FemtoLux 30	1030 nm 515 nm 343 nm	350 fs – 1 ps	> 27 W (typical 30 W)	4 MHz	100 µJ or 1 mJ	4
FemtoLux 3	1030 nm 515 nm	300 fs – 5 ps	3 W	10 MHz	3 µJ	14

¹⁾ At fundamental wavelength.

Due to the constant product improvements, EKSPILA reserves its right to change specifications without advance notice.



Learn more about EKSPILA



Latest information about Industrial Lasers
www.ekspla.com



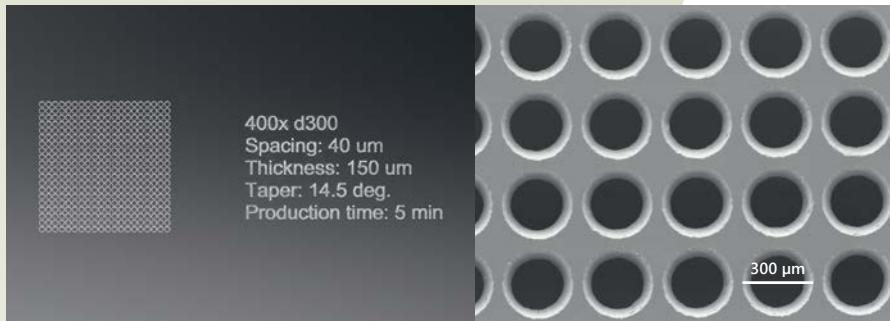
Material processing examples

Made with **FemtoLux 30** laser

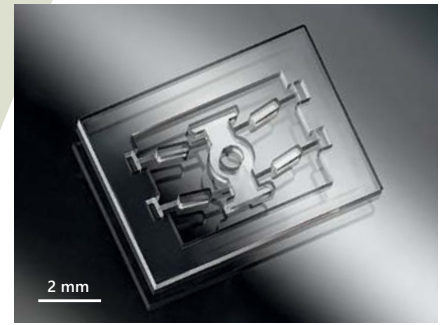
Transparent materials

Transparent materials, such as glass/sapphire are fascinating materials with remarkable properties that have made it a favorite among researchers and engineers for decades. Its robustness, chemical resistance, transparency, and affordability have made it an ideal candidate for a multitude of applications, ranging from microfluidic devices and optical components to electronic devices.

The femtosecond laser micromachining technique has brought transparent materials processing to the next level. Complex structures can now be precisely fabricated by selectively removing material through drilling, cutting, milling, etching and scribing.



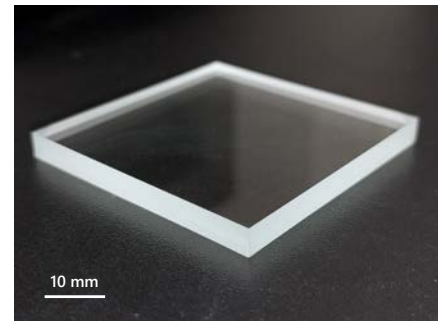
Borosilicate drilling. Courtesy of FTMC.



SLE of fused silica. Courtesy of Femtika.



UVFS milling. Courtesy of FTMC.



Laser-based Bessel beam scribing of soda-lime glass. Courtesy of FTMC.

Polymers

Polymers are revolutionizing various industries with their exceptional properties, including flexibility, durability, and ease of processing. These versatile materials find application in a wide range of fields, from aerospace and biomedicine to electronics. Polymer processing with femtosecond lasers has opened up new avenues for precision fabrication of complex structures by selectively removing polymer with high precision and minimal thermal effects.

Femtosecond laser processing can also be used for photo-polymerization, a process where monomers or prepolymers are selectively polymerized to create complex 3D structures with sub-micron resolution, high accuracy, and repeatability.

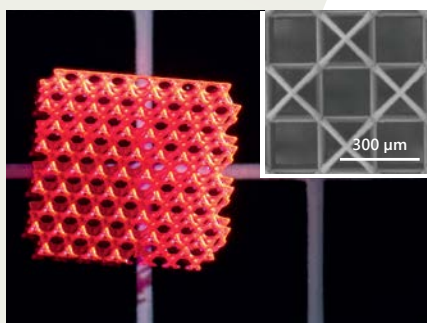


Photo-polymerization. Courtesy of Femtika.

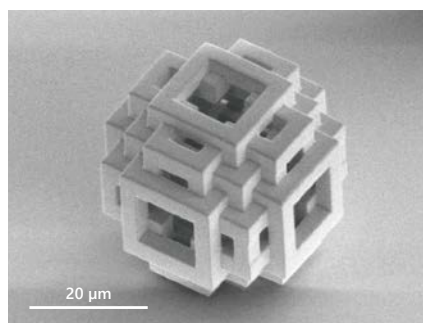
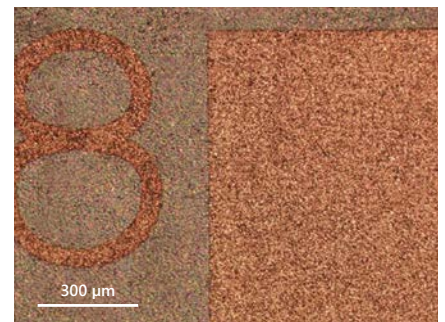
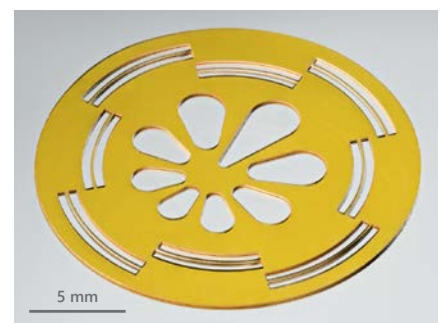


Photo-polymerization. Courtesy of WOP.



Insulation layer removal from PCB. Courtesy of FTMC.



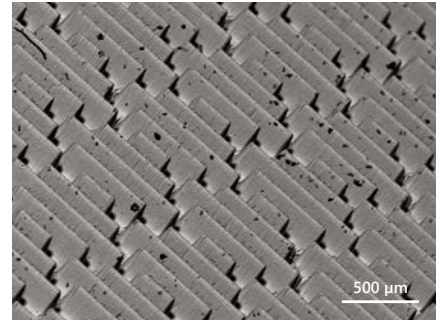
Polymide cutting. Courtesy of FTMC.

Material Processing Examples

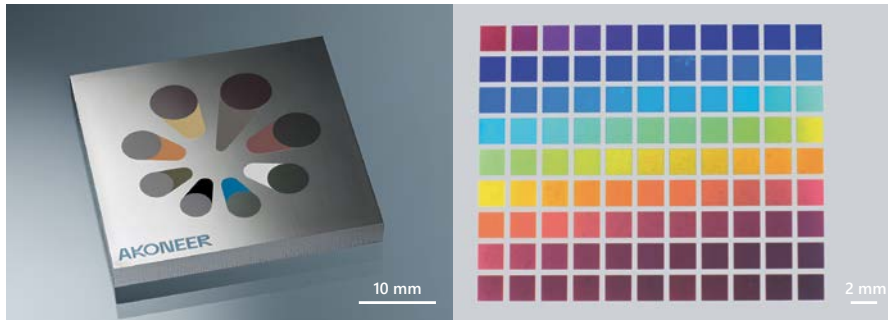
Metals

Metals, particularly stainless steel, has become an integral part of modern engineering and manufacturing thanks to its mechanical, chemical, and aesthetic properties. Its versatility has led to its use in diverse fields such as aerospace, automotive, architecture, and medical equipment.

Femtosecond laser technology has revolutionized metal micromachining, offering an exciting array of possibilities for creating visually stunning and intricately precise structures with minimal heat affected zones. Femtosecond lasers enable the production of complex shapes and features, while also providing the capability to perform black/white marking and coloring without the need for chemical additives.



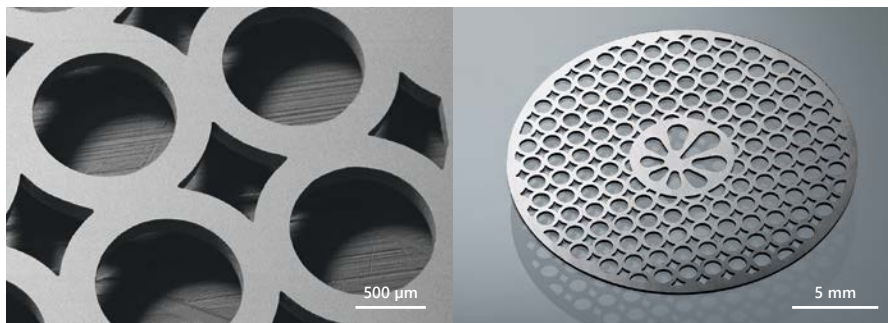
"Shark skin" surface structuring. Courtesy of FTMC.



Stainless steel (left) and titanium film (right) coloring with GHz burst feature. Courtesy of Akoneer.



Highly-resistant black marking. Courtesy of FTMC.

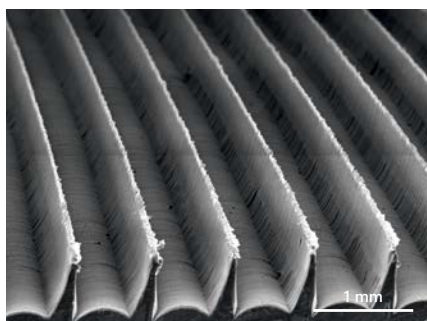


Stainless steel cutting. Courtesy of FTMC.

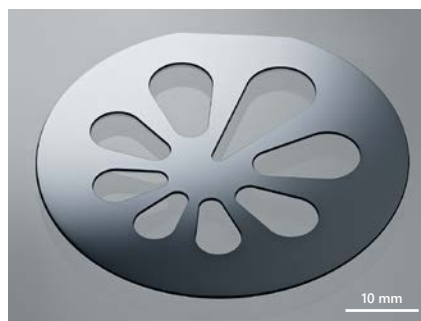


Stainless steel cutting. Courtesy of FTMC.

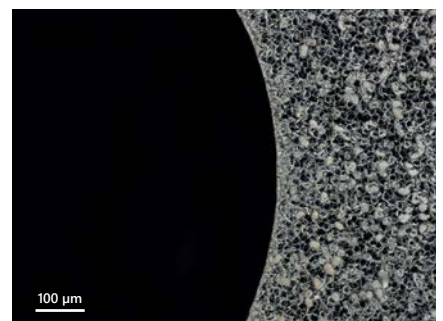
Other materials



Teflon (PTFE) milling. Courtesy of FTMC.



Crystalline silicon cutting. Courtesy of FTMC.



Crystalline silicon cutting. Courtesy of FTMC.

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Industrial
Femtosecond
Lasers

FemtoLux 30

Reliability Redefined

A reliable &
versatile tool for
micromachining

- / Glass, sapphire and ceramics
micro processing
- / Microelectronics manufacturing
- / Glass intra volume structuring
- / Micro processing of different
polymers and metals
- / LCD, LED, OLED drilling,
cutting and repair



Zero maintenance

2 years of total warranty

30 W Femtosecond Industrial Laser

FemtoLux 30

Designed from the get-go for maximum reliability, seamless integration and non-stop 24/7/365 zero maintenance operation with innovative "dry" cooling.

The FemtoLux 30 femtosecond laser has a tunable pulse duration from <350 fs to 1 ps and can operate in a broad AOM controlled range of pulse repetition rates from a single shot to 4 MHz.

The maximum pulse energy is more than 100 µJ operating with single pulses and can reach more than 450 µJ in burst mode, ensuring higher ablation rates and processing throughput for different materials.

The FemtoLux 30 beam parameters will meet the requirements of the most demanding materials and micro-machining applications.

Innovative laser control electronics ensure simple control of the FemtoLux 30 laser by external controllers that could run on different platforms, be it Windows, Linux or others using REST API commands.

This makes easy integration and reduces the time and human resources required to integrate this laser into any laser micromachining equipment.

Seamless User Experience

Easy integration – remote control using REST API via RS232 and LAN.

Reduced integration time – demo electronics is available for laser control programming in advance.

Easy and quick installation – no water, fully disconnectable laser head. Can be installed by the end-user.

Easy troubleshooting – integrated detectors and constant system status logging.

No periodic maintenance required.

Features

Typical max output power
30 W at 1030 nm,
11 W at 515 nm,
6 W at 343 nm

Typical max output energies
> 100 µJ at 1030 nm,
> 55 µJ at 515 nm,
> 30 µJ at 343 nm

High energy version available
(1 mJ at 10 kHz)

MHz, GHz, MHz+GHz burst
modes

> 450 µJ in a burst mode

< 350 fs – 1 ps

Single shot to 4 MHz
(AOM controlled)

Pulse-on-demand (PoD),
with jitter as low as 20 ns
(peak-to-peak)

<0.5% RMS power long term
stability over 100 hours

$M^2 < 1.2$

Beam circularity > 0.85

Zero maintenance

Dry cooling (no water used)

2 years of total warranty

At 1030 nm
30 W
>100 µJ

At 515 nm
11 W
>55 µJ

At 343 nm
6 W
>30 µJ



Learn more
about FemtoLux 30
www.ekspla.com

“Dry” Cooling

Direct Refrigerant Cooling System

The FemtoLux 30 laser employs an innovative cooling system and sets new reliability standards among industrial femtosecond lasers. No additional bulky and heavy water chiller is needed.

The chiller requires periodic maintenance – cooling system draining and rinsing and water and particle filter replacement. Moreover, water leakage can cause damage to the laser head and other equipment. Instead of using water for transferring heat from a laser head, the FemtoLux 30 laser uses an innovative Direct Refrigerant Cooling method.

The refrigerant agent circulates from a PSU-integrated compressor and condenser, to a cooling plate via armored flexible lines.

The entire cooling circuit is permanently hermetically sealed and requires no maintenance.



See **FemtoLux 30** introduction video showing “dry cooling” advantages

Benefits

Military-grade reliability

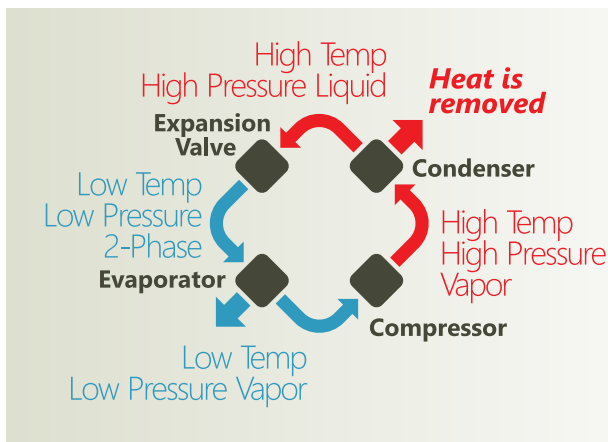
Permanently hermetically sealed system **>90,000 hour MTBF**

No maintenance

High cooling efficiency

>45% lower power consumption compared to water cooling equipment

Compact and light



Compressor picture. Courtesy of Aspen Systems Inc.

Simple & Reliable Cooling Plate Attachment

The cooling plate is detachable from the laser head for more convenient laser installation. The laser cooling equipment is integrated with the laser power supply unit into a single 4U rack-mounted housing with a total weight of 15 kg.

Detachable cooling plate

Integrated cooling equipment with the laser power supply



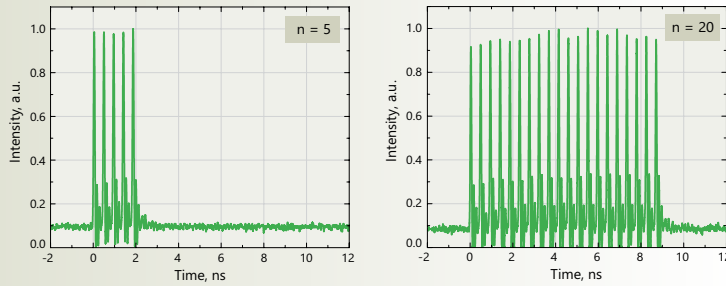
Simple and reliable cooling plate attachment

GHz Burst Option

Patent-Pending Method
for Ultra-High Rate Bursts

Short GHz burst

Fig 1. Measured 2.2 GHz intra-burst PRR burst of pulses containing a different number of pulses of equal amplitudes at 31.5 W average output power



Long GHz burst

Fig 2. Measured 2.2 GHz pre-shaped bursts of 1000 pulses at 233 kHz burst repetition rate for the desired rectangular-like burst shape

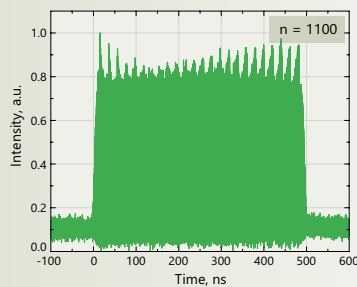
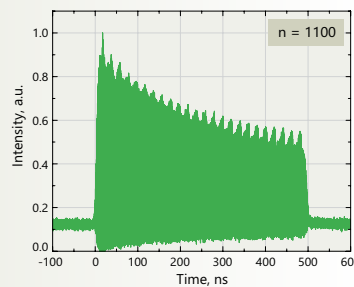


Fig 3. Measured 2.2 GHz non-pre-shaped bursts of 1100 pulses at 233 kHz burst repetition rate



MHz + GHz burst mode

Fig 4. Measured 4 bursts of 50 MHz BRR containing 4 pulses of 2.5 GHz intra-burst PRR

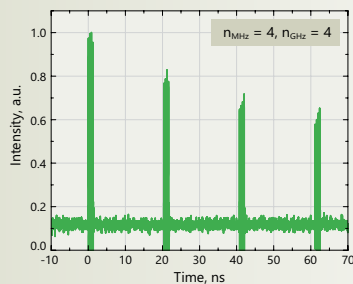
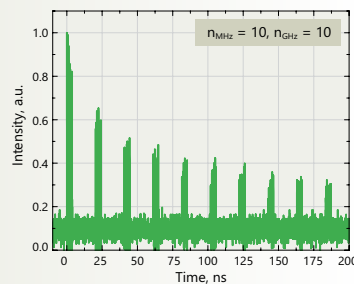


Fig 5. Measured 10 bursts of 50 MHz BRR containing 10 pulses of 2.5 GHz intra-burst PRR



Benefits

The Femtolux 30 laser can operate in the **single-pulse** mode, **MHz burst** mode, **GHz burst** mode, and **MHz + GHz burst** mode.

The burst formation technique based on the use of the AFL is a very versatile method as it allows to overcome many limitations encountered by other fiber- and/or solid-state-based techniques.

Any desired intra-burst PRR can be achieved independently from the initial PRR of the master oscillator

Identical pulse separation inside the GHz bursts is maintained

Short- and long-burst formation modes can be provided.

/ A short burst is up to about 10 ns burst width (from 2 to tens of pulses in the GHz burst).

/ A long burst is from ~20 ns up to a few hundred ns in burst width (from tens to thousands of pulses in the GHz burst)

MHz+GHz burst mode

An adjustable amplitude envelope of the GHz bursts is provided

No pre/post pulses in GHz burst. Pure GHz bursts

Ultrashort pulse duration is maintained inside the bursts

A new versatile patent-pending method to form ultra-high repetition rate bursts of ultrashort laser pulses.

The developed method is based on the use of an all-in-fiber active fiber loop (AFL). A detailed description of the invention can be found on:

[1] Andrejus Michailovas, and Tadas Bartulevičius. 2021 Int. patent application published under the Patent Cooperation Treaty (PCT) WO2021059003A1.

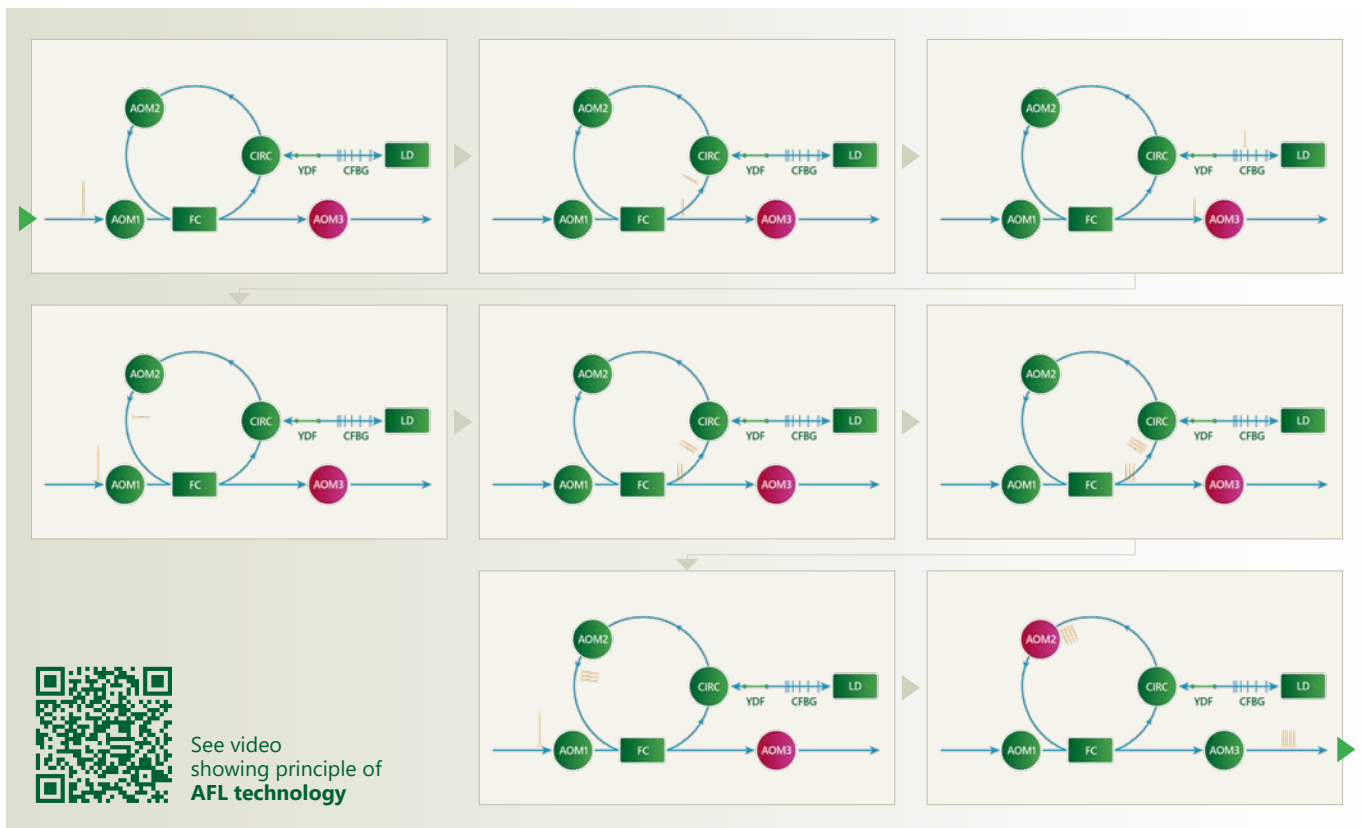
[2] Tadas Bartulevičius, Mykolas Lipnickas, Virginija Petrauskienė, Karolis Madeikis, and Andrejus Michailovas, (2022), "30 W-average-power femtosecond NIR laser operating in a flexible GHz-burst-regime," Opt. Express 30, 36849-36862.

Specifications

Parameter	Value	
Burst repetition rate	200 – 650 kHz	
Intra-burst pulse repetition rate ¹⁾	2 GHz	
GHz burst mode	short	long
Number of pulses ²⁾	2 – 22	44 – 1100
Shape	square, rising, falling	falling, pre-shaped ³⁾
MHz + GHz burst mode		
Burst repetition rate	100 – 650 kHz	
Number of pulses in MHz burst	2 – 10	
Number of pulses in GHz burst	2 – 22	

¹⁾ Custom intra-pulse PRR is available upon a request.
²⁾ Depends on the intra-pulse PRR.
³⁾ For more information, please inquire sales@ekspla.com.

Principle of AFL Technology

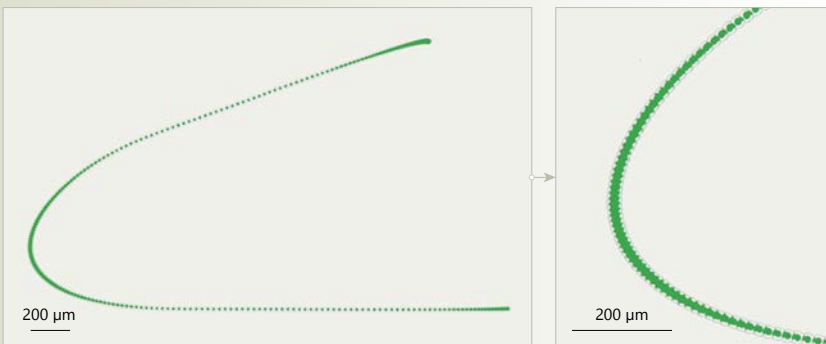


Pulse-on-Demand (PoD)

Traditional laser triggering techniques struggle to maintain equally spaced pulses at high speeds (Fig.1, 2). Pulse-on-demand feature tackles this challenge and enables high-speed micromachining (Fig. 3).

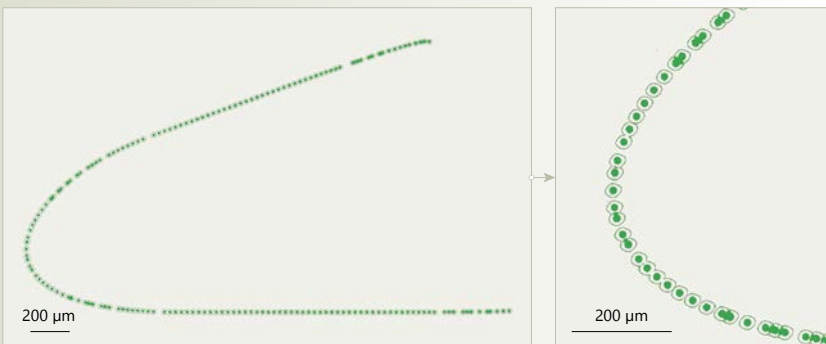
Time based laser triggering

Fig 1. Complex shape scanned with time based laser triggering mode with a pulse repetition of 200 kHz and scanning speed of 6 m/s. The scanning started from the top right to the bottom right area. Overlapping pulses result in an overheated area.



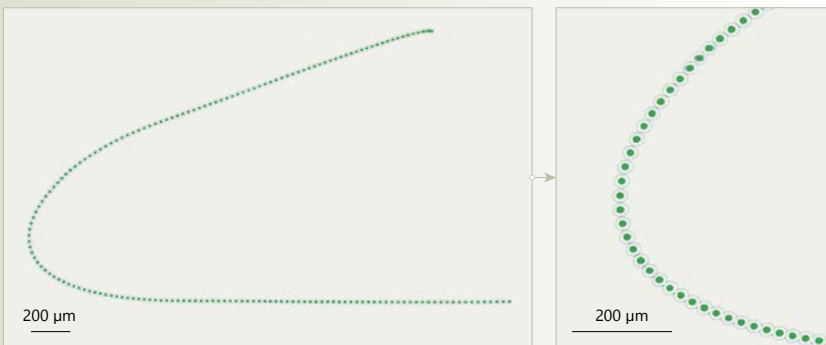
Position based laser triggering

Fig 2. Complex shape scanned with position based laser triggering mode with a pitch of 30 µm and scanning speed of 6 m/s. The scanning started from the top right to the bottom right area. Jitter of tens of µs results in random pulse spacing.



Pulse-on-demand (PoD)

Fig 3. Complex shape scanned with pulse-on-demand (PoD) and position based laser triggering mode with a pitch of 30 µm and scanning speed of 6 m/s. The scanning started from the top right to the bottom right area. PoD feature preserves equidistant pulse spacing at high speeds.



Benefits

Jitter lower than 20 ns ensures consistent and equidistant pulse spacing for high-speed micromachining

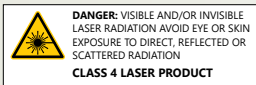
Adjustable repetition rate for processing complex geometries

Faster processing speeds, increased productivity

PoD feature enables the laser to fire a pulse only when required, rather than at a constant rate, enabling precise control over the laser's output and resulting in higher efficiency, accuracy and quality.

This capability is especially valuable in various micromachining applications where a high processing speed, constant energy, and accuracy are essential. To follow complex curvature at high speed and to maintain equidistant spacing it is necessary to ensure that the repetition rate of the pulses is adjusted. To achieve these requirements, it is necessary to ensure that the repetition rate of the pulses is adjusted to follow complex curvature at high speed and to maintain equidistant spacing. One may try to use position based laser triggering but, due to laser system limitations, the jitter will be from several µs to tens of µs, which will result in random spacing of the pulses. On the other hand, the usage of time based laser triggering results in overheat areas, due to excessive overlap of pulses. The FemtoLux 30 laser has the pulse-on-demand feature with jitter as low as 20 ns (peak-to-peak), and it can therefore tackle all the challenges and maximize process efficiency, precision and quality at high speed.

Specifications ¹⁾

Model	FemtoLux 30	
Main specifications		
Central wavelength	fundamental	1030 nm
	with second harmonic option	515 nm
	with third harmonic option	343 nm
Pulse repetition rate (PRR) ²⁾	200 kHz – 4 MHz	
Pulse repetition frequency (PRF) after frequency divider	PRF = PRR / N, N=1, 2, 3, ... , 65000; single shot	
Average output power	at 1030 nm	> 27 W (typical 30 W)
	at 515 nm	> 11 W ³⁾
	at 343 nm	> 6 W ³⁾
Pulse energy	at 1030 nm	> 100 µJ or 1 mJ ⁴⁾
	at 515 nm	> 55 µJ ³⁾
	at 343 nm	> 30 µJ ³⁾
Number of pulses in MHz burst ⁵⁾	2 – 10	
Total energy in burst mode	> 450 µJ ⁶⁾	
Power long term stability (Std. dev.) ⁷⁾	< 0.5 %	
Pulse energy stability (Std. dev.) ⁸⁾	< 1 %	
Pulse duration (FWHM)	tunable, < 350 fs ⁹⁾ – 1 ps ¹⁰⁾	
Beam quality	M ² < 1.2 (typical < 1.1)	
Beam circularity, far field	> 0.85	
Beam divergence (full angle)	< 1 mrad	
Beam pointing thermal stability	< 20 µrad/°C	
Beam diameter (1/e ²) at 20 cm distance from laser aperture at 1030 nm	2.5 ± 0.4 mm	
Triggering mode	internal / external	
Pulse output control	frequency divider, pulse picker, burst mode, packet triggering, power attenuation, pulse-on-demand ¹¹⁾	
Control interfaces	RS232 / LAN	
Length of the umbilical cord	3 m, detachable. Custom length option available	
Laser head cooling type	dry (direct refrigerant cooling through detachable cooling plate)	
Physical characteristics		
Laser head (W × L × H)	429 × 569 × 130 mm	
Power supply unit (W × L × H)	449 × 376 × 177 mm	
Operating requirements		
Mains requirements	100 – 240 V AC, single phase, 50/60 Hz	
Maximal power rating	800 W	
Operating ambient temperature	18 – 27 °C	
Relative humidity	10–80 % (non-condensing)	
Air contamination level	ISO 9 (room air) or better	
<p>¹⁾ Due to continuous improvement, all specifications are subject to change without notice. Parameters marked typical are not specifications. They are indications of typical performance and will vary with each unit we manufacture. All parameters are specified for a shortest pulse duration. Unless stated otherwise, all specifications are measured at 1030 nm and for basic system without options.</p> <p>²⁾ When frequency divider is set to transmit every pulse. Fully controllable by integrated AOM.</p> <p>³⁾ At 200 kHz.</p> <p>⁴⁾ Other combinations of energy and repetition rate available.</p> <p>⁵⁾ Oscillator frequency ~50 MHz, ~20 ns separation between pulses.</p> <p>⁶⁾ > 450 µJ in MHz burst mode or MHz+GHz burst mode at 100 kHz PRR. > 90 µJ energy in GHz burst mode.</p> <p>⁷⁾ Over 100 h after warm-up under constant environmental conditions.</p> <p>⁸⁾ Under constant environmental conditions.</p> <p>⁹⁾ At PRR > 500 kHz. At PRR < 500 kHz shortest pulse duration is < 400 fs.</p> <p>¹⁰⁾ Custom pulse duration by request. For example – fixed 50 fs available.</p> <p>¹¹⁾ Jitter < 20 ns. Trigger-to-pulse delay < 1 µs.</p>		
		 <p>DANGER: VISIBLE AND/OR INVISIBLE LASER RADIATION AVOID EYE OR SKIN EXPOSURE TO DIRECT, REFLECTED OR SCATTERED RADIATION CLASS 4 LASER PRODUCT</p>

Performance

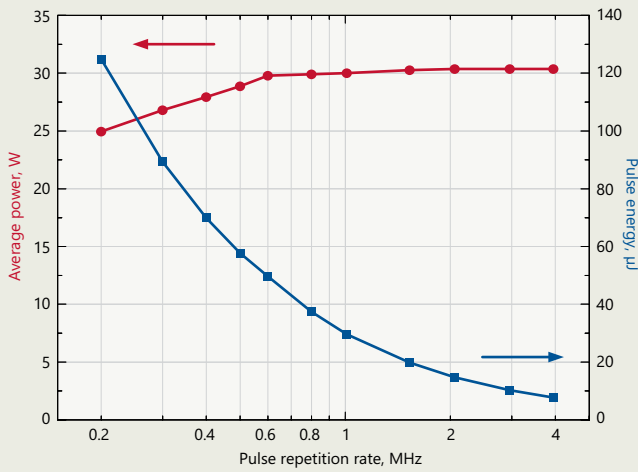


Fig 1. Typical dependence of output power and pulse energy of FemtoLux 30 laser at 1030 nm on pulse repetition rate

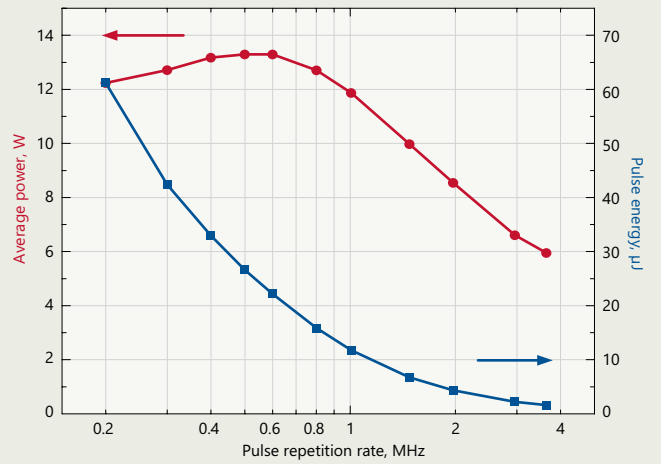


Fig 2. Typical dependence of output power and pulse energy of FemtoLux 30 laser at 515 nm on pulse repetition rate

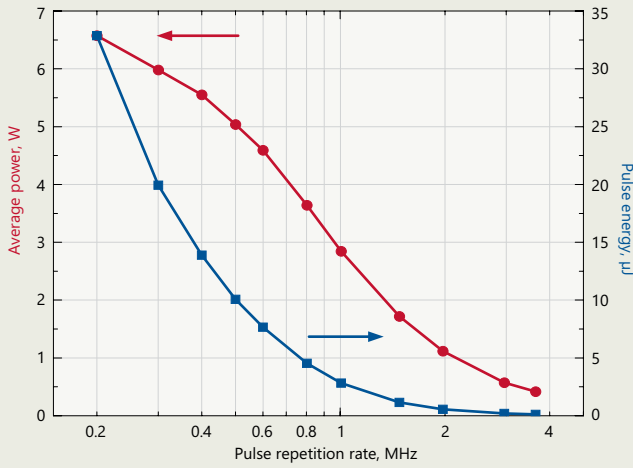


Fig 3. Typical dependence of output power and pulse energy of FemtoLux 30 laser at 343 nm on pulse repetition rate

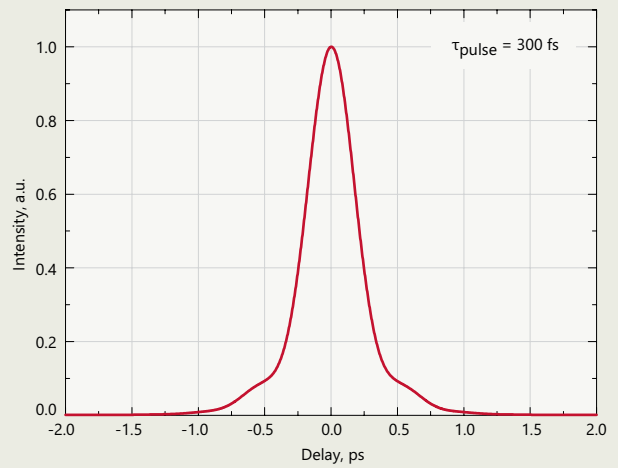


Fig 4. Typical FemtoLux 30 laser (at 1030 nm) output pulse autocorrelation function

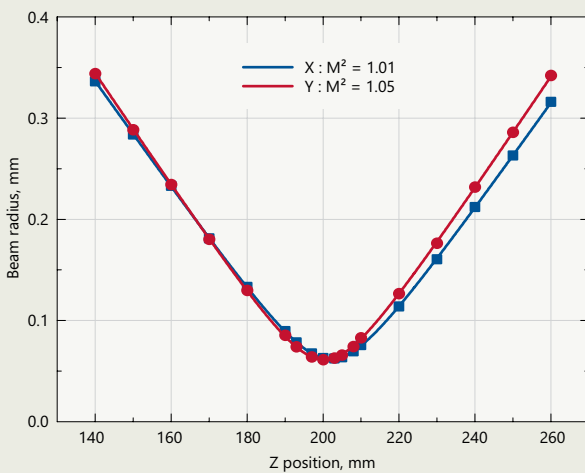


Fig 5. Typical M^2 measurement of FemtoLux 30 laser at 1030 nm

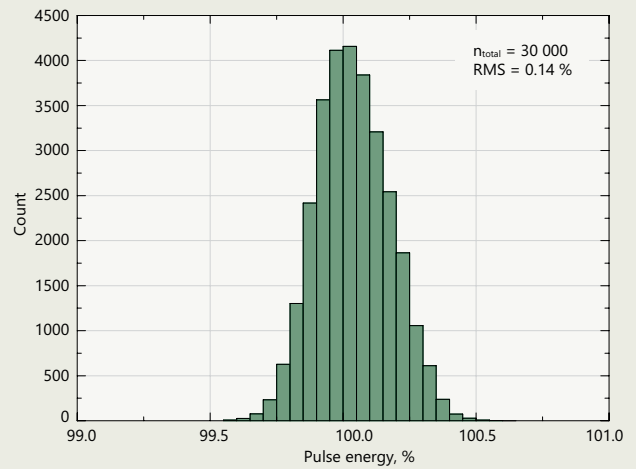


Fig 6. Typical pulse-to-pulse energy stability of FemtoLux 30 laser at 200 kHz over 30 000 pulses. RMS was calculated by using a set of mean values of 10 consecutive laser shots

FemtoLux 30

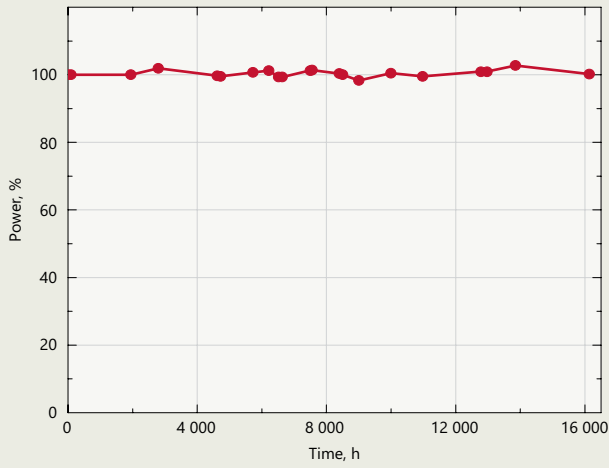


Fig 7. Long-term average power stability of the FemtoLux 30 laser at 1030 nm under constant environmental conditions over an extended duration of 16,000 hours

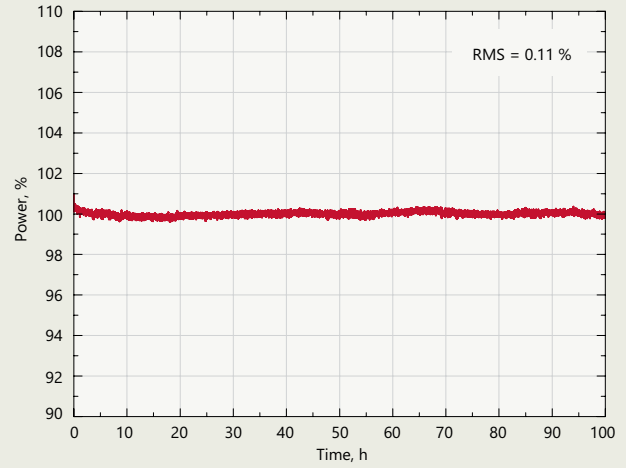


Fig 8. Typical long term average power stability of FemtoLux 30 laser at 1030 nm under constant environmental conditions

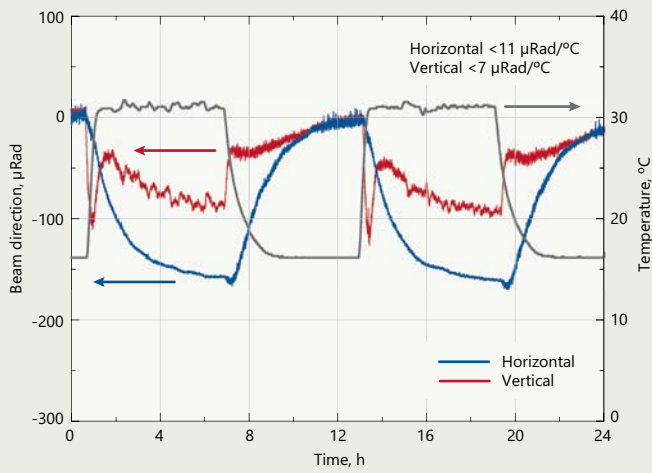


Fig 9. Typical beam direction stability of FemtoLux 30 under harsh environmental conditions

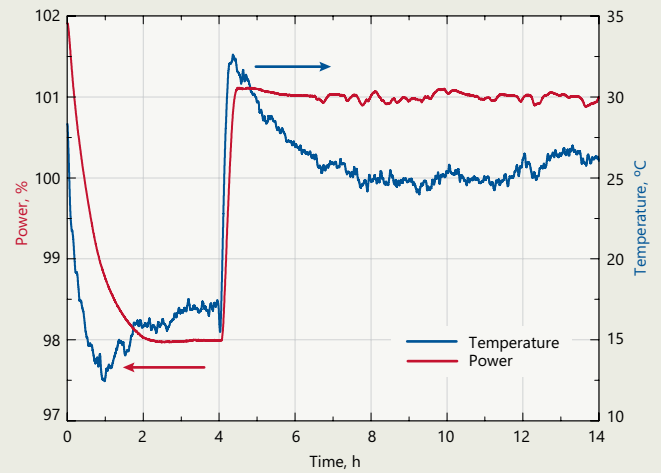


Fig 10. Average output power dependence of FemtoLux 30 laser on ambient temperature at 1030 nm



FemtoLux 30 with harmonics module and power supply

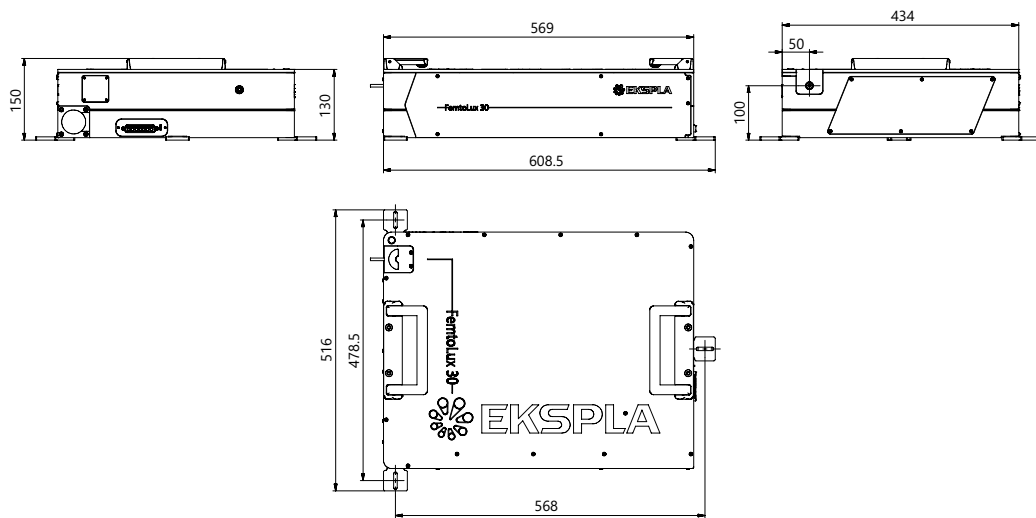


Fig 11. FemtoLux 30 laser head outline drawing

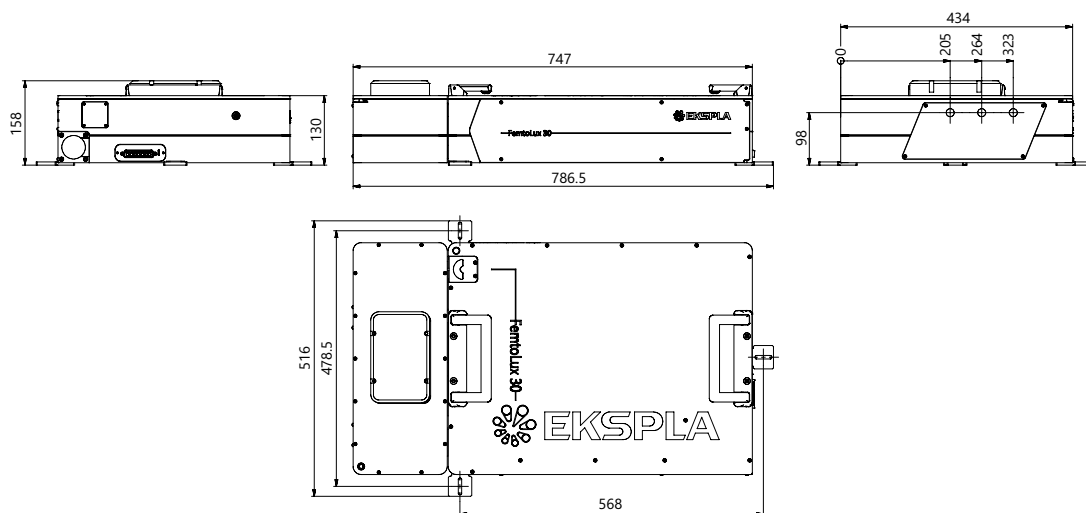


Fig 12. FemtoLux 30 with harmonics module. Laser head outline drawing

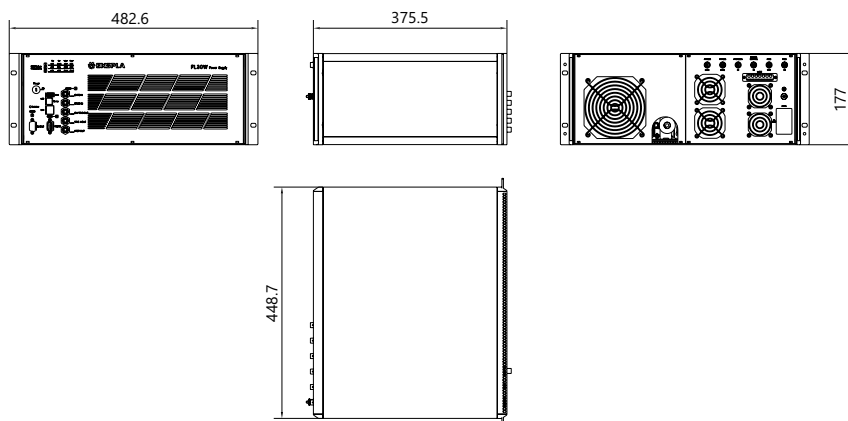


Fig 13. Power supply outline drawing

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Industrial
Femtosecond
Lasers

FemtoLux 3

Applications

- / Inner volume marking of transparent materials
- / Marking and structuring
- / Micromachining of brittle materials
 - / Photopolymerization
- / Ophthalmologic surgery
 - / Biological Imaging
- / Pumping of femtosecond OPO/OPA
 - / Microscopy



Microjoule Class Femtosecond Industrial Lasers

FemtoLux 3

FemtoLux 3 is a modern femtosecond fiber laser aimed for both R&D use and industrial integration.

Tunable pulse duration in a range of 300 fs – 5 ps, adjustable pulse repetition rate up to 10 MHz and adjustable pulse energy up to 3 μ J allows optimization of laser parameters for the desired application. These include marking and volume structuring of transparent materials, photopolymerization, biological imaging, nonlinear microscopy and many others. To expand the scope of applications even further this laser can be equipped with a second harmonics module.

With burst mode enabled, FemtoLux 3 can generate bursts of pulses with energy above 10 μ J which can significantly improve the efficiency of processes.

Having a rigid, compact, passive air-cooled laser head and the possibility to control the laser from a wireless tablet, FemtoLux 3 can be integrated with different equipment, be it laser equipment for material micro-processing, microscopy or any other research equipment.



FemtoLux 3 laser with second harmonic option

Features

Output power
**3 W at 1030 nm,
1.2 W at 515 nm**

Up to **3 μ J/pulse** and
10 μ J/burst (at 1030 nm)

Up to **1.2 μ J/pulse** and
5 μ J/burst (at 515 nm)

< 300 fs ... 5 ps
tunable pulse duration

$M^2 < 1.2$

Versatile laser control and
synchronisation capabilities

Up to **10 MHz**
pulse repetition rate

Smart triggering for
synchronous operation with
polygon scanner and PSO

Instant amplitude control

Passive air cooling of the laser
head

24/7 operation

At 1030 nm

At 515 nm

Output power

3 W

1.2 W

Pulse energy

3 μ J

1.2 μ J

Burst mode

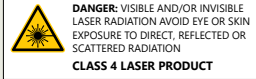
10 μ J

5 μ J



Learn more
about FemtoLux 3
www.ekspla.com

Specifications ¹⁾

Model		FemtoLux 3
Main specifications		
Central wavelength	fundamental	1030 nm
	with second harmonic option	515 nm
Minimal pulse duration (FWHM) at 1030 nm		< 300 fs (typical ~230 fs)
Pulse duration tuning range		300 fs – 5 ps
Maximal average output power ²⁾	at 1030 nm	> 3 W
	at 515 nm	> 1.2 W
Power long term stability (Std. dev.) ³⁾		≤ 0.5 %
Maximal pulse energy ²⁾	at 1030 nm	> 3 μJ
	at 515 nm	> 1.2 μJ
Pulse energy stability (Std. dev.) ⁴⁾		< 2 %
Laser pulse repetition rate (PRR _i) range ⁵⁾		1 – 10 MHz
Pulse repetition rate after pulse picker		PRR = PRR _i / N, N=1, 2, 3, ... , min 10 kHz
External pulse gating		via TTL input
Burst mode ⁶⁾		1 – 10 pulses
Max burst energy	at 1030 nm	> 10 μJ
	at 515 nm	> 5 μJ
Burst shape control		via analog input
Power attenuation		0 – 100 % from remote control application or via analog input
Polarization orientation		linear, vertical
Polarization extinction ratio		> 1000:1
M ²		< 1.2
Beam divergence (full angle)		< 1.0 mrad
Beam circularity (far field)		> 0.85
Beam pointing stability (pk-to-pk) ⁷⁾		< 30 μrad
Beam diameter (1/e ²) at 20 cm distance from laser aperture	at 1030 nm	2.0 ± 0.3 mm
	at 515 nm	1.0 ± 0.2 mm
Operating requirements		
Mains requirements		100–240 V AC, single phase 47–63 Hz
Maximal power consumption		< 500 W
Operating ambient temperature		15 – 30 °C
Relative humidity		10 – 80 % (non-condensing)
Air contamination level		ISO 9 (room air) or better
Physical characteristics		
Cooling of the laser head		air, passive
Laser head size (L×W×H)	at 1030 nm	464 × 363 × 129 mm
	at 515 nm	620 × 363 × 129 mm
Power supply unit size (L×W×H)	stand-alone	449 × 436 × 140 mm
	19" rack mountable	483 × 436 × 140 mm
Umbilical length		5 m
Classification		
Classification according EN60825-1		CLASS 4 laser product
<p>¹⁾ Due to continuous improvement, all specifications are subject to change without notice. Parameters marked typical are not specifications. They are indications of typical performance and will vary with each unit we manufacture.</p> <p>²⁾ See typical power and energy curves for other pulse repetition rates at Fig 1, Fig 2. and Fig 4.</p> <p>³⁾ At 1 MHz PRR_i during 24 h of operation after warm-up under constant environmental conditions.</p> <p>⁴⁾ At 1 MHz PRR_i under constant environmental conditions.</p> <p>⁵⁾ When pulse picker is set to transmit every pulse.</p> <p>⁶⁾ Pulse separation inside the burst is about 20 ns.</p> <p>⁷⁾ Beam pointing stability is evaluated as a movement of the beam centroid in the focal plane of a focusing element.</p>		
		

Performance

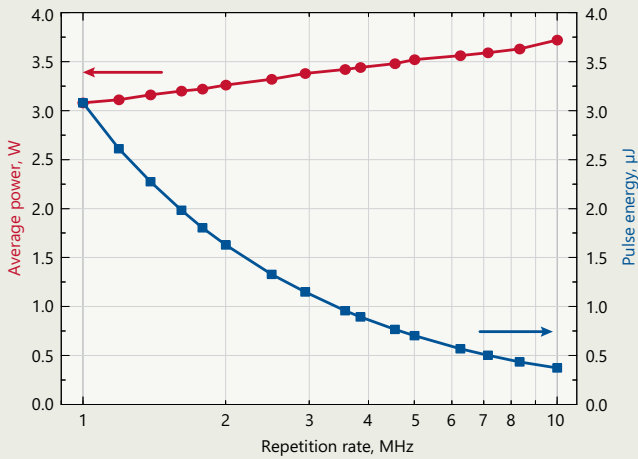


Fig 1. Typical dependence of output power and pulse energy of FemtoLux 3 laser at 1030 nm when changing internal repetition rate of the laser

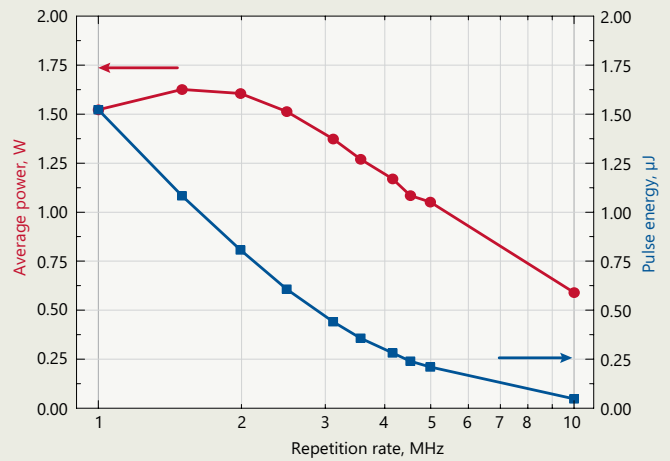


Fig 2. Typical dependence of output power and pulse energy of FemtoLux 3 laser at 515 nm on pulse repetition rate

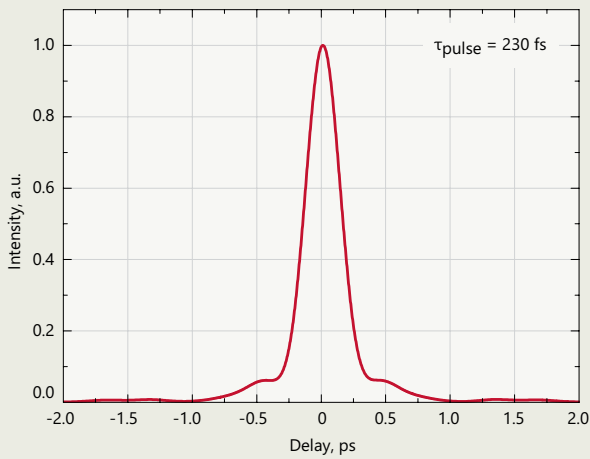


Fig 3. Typical FemtoLux 3 laser (at 1030 nm) output pulse autocorrelation function at 3 μJ pulse energy. Calculated pulse duration is 230 fs

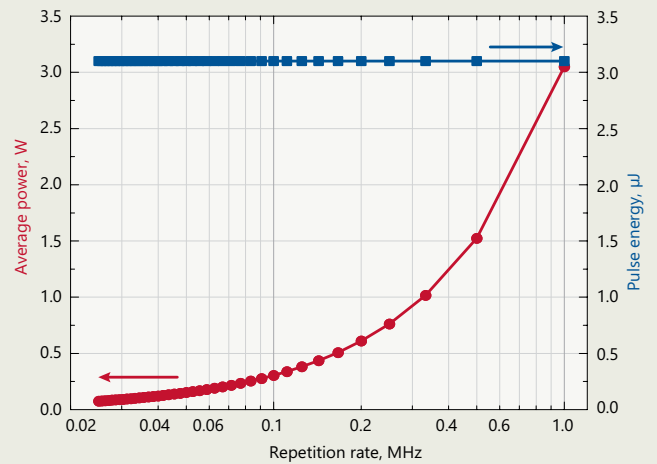


Fig 4. Typical dependence of output power and pulse energy of FemtoLux 3 laser at 1030 nm when repetition rate is reduced by pulse picker. Internal repetition rate of the laser in this case is 1 MHz

FemtoLux 3

Stability

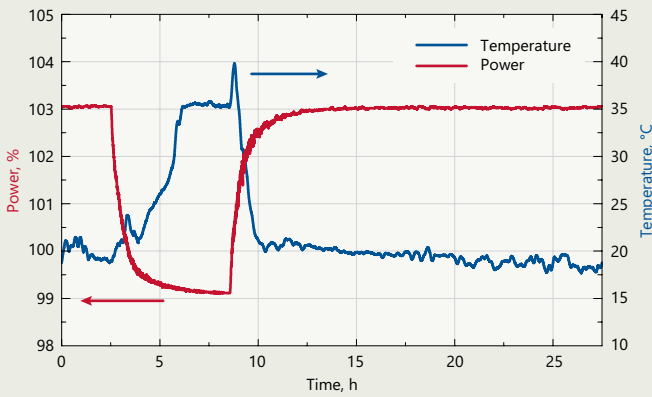


Fig 5. Average output power dependence on ambient temperature at 1030 nm

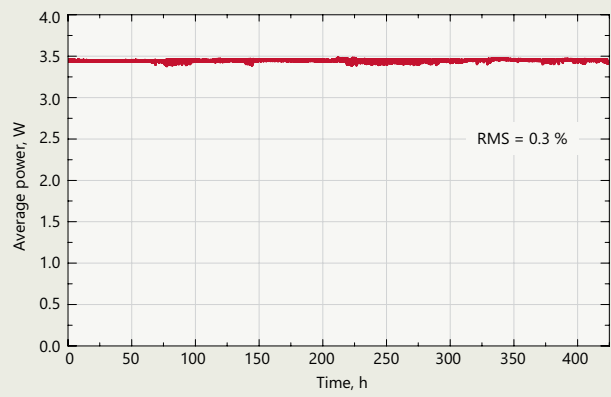


Fig 6. Typical long term average output power stability of FemtoLux 3 laser at 1030 nm under constant environmental conditions

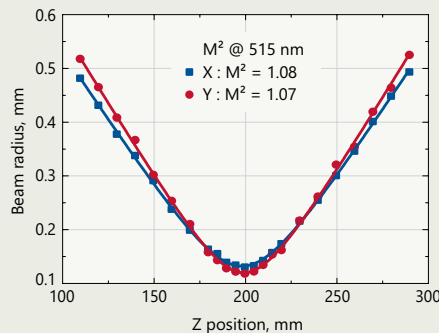
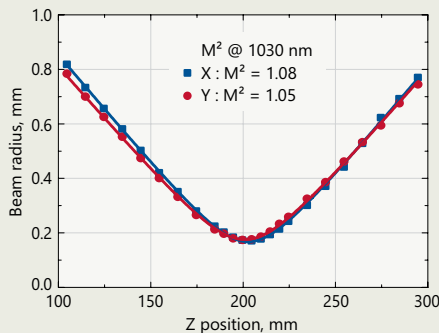


Fig 7. Typical M² measurement of FemtoLux 3 at 1030 nm (left) and 515 nm (right)

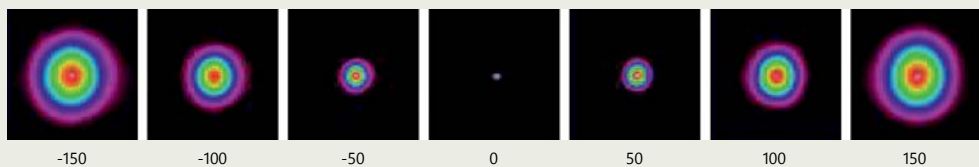


Fig 8. Typical beam profiles along propagation axis of FemtoLux 3 series laser

Laser control application

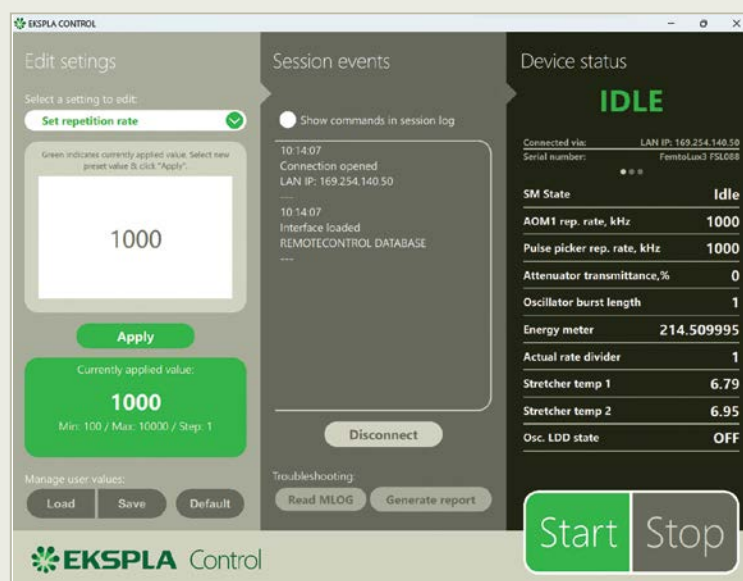


Fig 9. Example of FemtoLux 3 laser control application

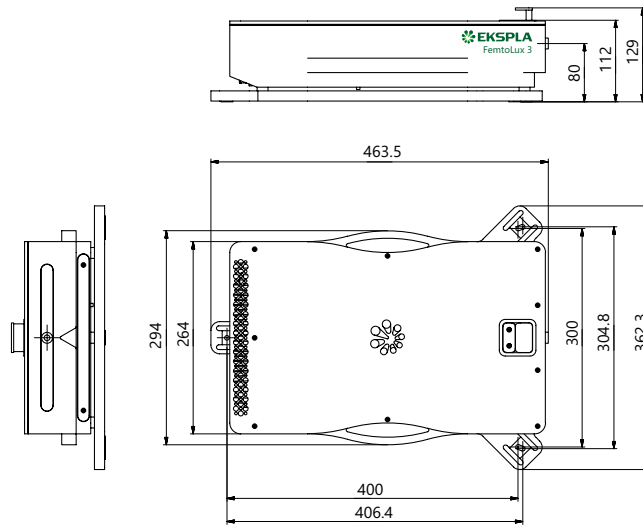


Fig 11. Outline drawings of FemtoLux 3 laser head

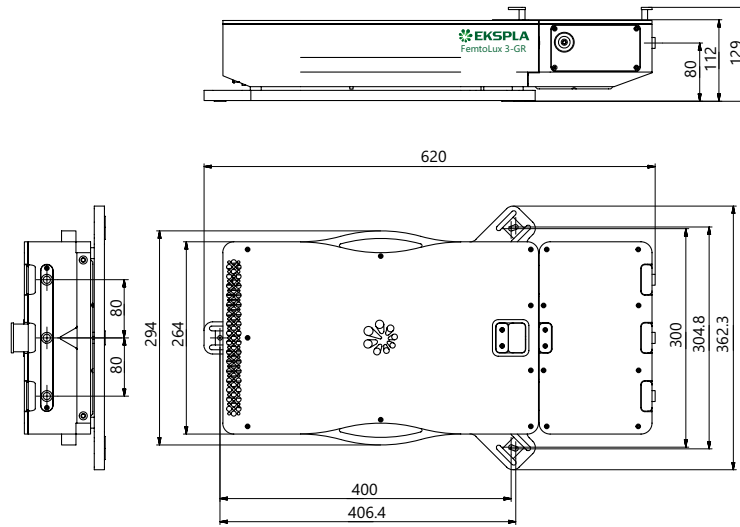


Fig 12. Outline drawings of FemtoLux 3 laser head with second harmonic option

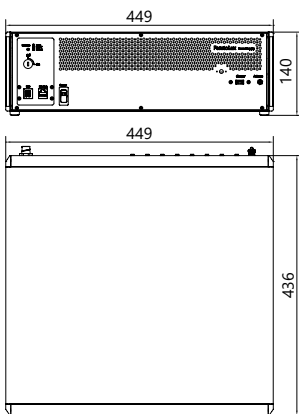


Fig 13. Outline drawings of FemtoLux 3 stand-alone control unit

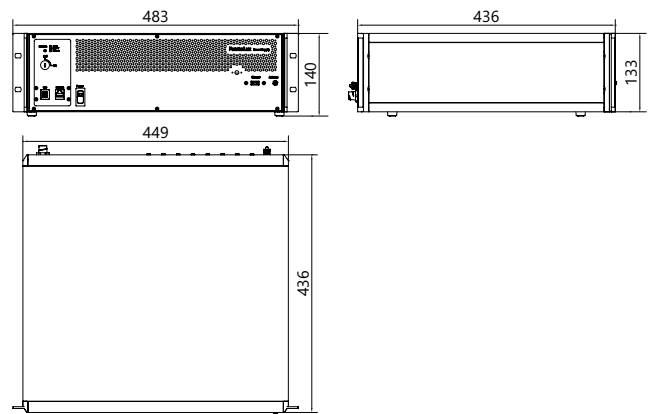


Fig 14. Outline drawings of FemtoLux 3 19" rack mountable control unit

Ordering Information

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